

IN THE CLAIMS:

1. (Currently Amended) A cleaning apparatus for cleaning a member used in the semiconductor field, the apparatus comprising:

an endless conveyor comprising a plurality of belt sections, each belt section being located at a spaced location from an adjacent belt section;

5 a housing, said endless conveyor extending through said housing;

an air curtain producing means for producing an air curtain at one end of said housing;

a first water curtain producing means for producing a first water curtain in said housing;

a second water curtain producing means for producing a second water curtain in said housing;

10 a third water curtain producing means for producing a third water curtain in said housing, said air curtain and said first water curtain defining a precleaning section of said housing, said first water curtain and said second water curtain defining a cleaning section of said housing, said second water curtain and said third water curtain defining a rinsing section of said housing, said third water curtain and another end of said housing defining a drying section of
15 said housing;

a first plurality of first nozzles located in said precleaning section;

a second plurality of second nozzles located in said cleaning section of said housing, said member being cleaned with one of said second nozzles disposed in an upward direction and another of said second nozzles disposed in a downward direction;

20 a third plurality of third nozzles located in said rinsing section of said housing; and

a jet mechanism for jetting a cleaning liquid in a mist state with a high pressure from said second plurality of second nozzles to the member to be cleaned, wherein a pressure of the jetted cleaning liquid is in the range of from 0.2 to 0.4 Mpa, said cleaning liquid being jetted in such a way that a gas is mixed into the cleaning liquid in a liquid state.

2. (Canceled)

3. (Previously Presented) The cleaning apparatus according to claim 1, wherein particle size of the jetted cleaning liquid is 100 μm or less.

4 - 5. (Canceled)

6. (Previously Presented) The cleaning apparatus according to claim 1, wherein the cleaning liquid is pure water added with surfactant.

7. (Previously Presented) The cleaning apparatus according to claim 1, wherein the cleaning liquid is pure water.

8 - 24. (Canceled)